

TEL Mark7 Clean Track System

1. System Brief

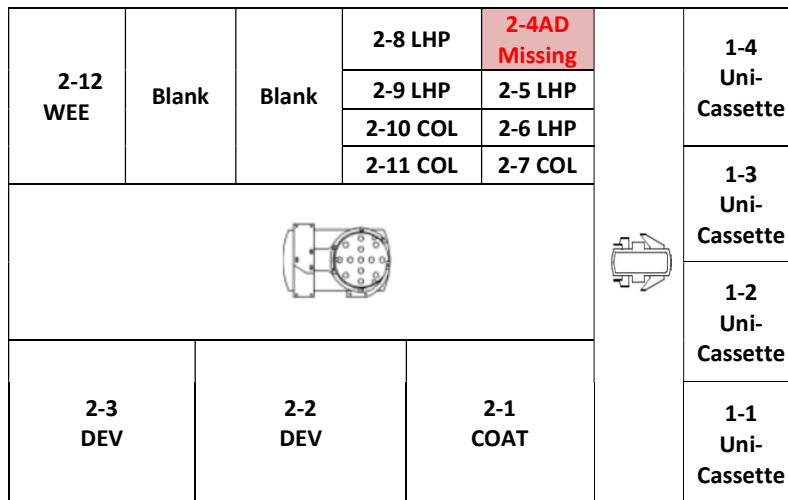
- A. Manufacturer: Tokyo Electron
- B. Model: Limited MARK7
- C. Wafer Size: 8-inch

- E. Year of Manufacture: August-1995
- F. Status: In warehouse

2. System Configuration

1-Photo Resist Coat and 2-Develop System

A. Block Diagram (Right to Left Wafer Flow)



Spin Motor Driver Thermo controller
Chemical Supply System Solvent Supply System Photo Resist Supply System

T&H Controller (1Cup)

UPS

AC POWER BOX

B. General Configuration

- a. Wafer Size: 200mm, Single Block System
- b. Wafer Flow: Right to Left (Off-Line)
- c. Process Block: 1ea (Single Block System)
- d. Block #1
 - d-1. TEL Clean Track Mark 8 FC-9801F Controller
 - d-2. Stage/Indexer: Non SMIF/Open Uni-Cassette CS/Cassette Station

d-3. CSA/Cassette Station Arm: 1ea.

- Block #2

e-1. Normal Photo Resist Coat 2-1 Unit

3 Normal Photo Resist Dispense Nozzles: Missing pump

1 Solvent Pre-wet RRC/Reduced Resist Coat Nozzle: Missing

1 Side Rinse Nozzle (Programmable Side Rinse EBR)

- Missing Dual Back Rinse Nozzles

Photo Resist Temperature Control: Installed

Motor Flange Temperature Control: Installed

- Missing Circulator Pump

- Missing Spin Motor

- Missing Cup

Photo Resist Drain Type: Direct Gravity Drain Type

Photo Resist Bottle Quantity: 6ea.

Photo Resist Auto Exchange: N/A

Auto Dummy Dispense System: Installed

e-2. Develop 2-2 Unit

Stream Nozzle (E2 Nozzle Bath type)

2-Rinse Nozzle

Dual Back Rinse Nozzles

Develop Temperature Control: Installed

Motor Flange Temperature Control: Installed

- Missing Spin Chuck

Drain Type: Direct Gravity Drain Type

Auto Damper: Installed

Auto Dummy Dispense System: Installed

Cup Type: Stainless Steel for Upper Cup and PP for Inner Cup

e-3. Develop 2-3 Unit

Stream Nozzle (E2 Nozzle Bath type)

2-Rinse Nozzle

Dual Back Rinse

Develop Temperature Control: Installed

Motor Flange Temperature Control: Installed

- Missing Circulator Pump

Drain Type: Direct Gravity Drain Type

Auto Damper: Installed

Auto Dummy Dispense System: Installed

Cup Type: Stainless Steel for Upper Cup and PP for Inner Cup

- f. THC/Temperature and Humidity Controller: 1ea
TEL OEM SHINWA T&H (1Cup)
- g. TEL OEM SMC Multi Controller: 1ea at External Chemical Supply Rack
- h. External Solvent and Develop Solutions Chemical Supply System
 - h-1. 1st. Section: Solvent Supply System
 - Solvent Chemical Type: 1ea.
 - CSSS to Auto Supply System with Two of Buffer Tanks
 - Tank Type: 2 Buffer Tanks (3 Liter/Tank, Teflon)
 - Tank Auto Switch-off/Exchange: Installed
 - h-2. 2nd. Section: Develop Supply System
 - Develop Solution Chemical Type: 1ea.
 - CSSS to Auto Supply System with Two of Buffer Tanks
 - Tank Type: 2 Buffer Tanks (3 Liter/Tank, Teflon)
 - Tank Auto Switch-off/Exchange: Installed
 - h-3. 3rd. Section: Photo Resist Supply System for Normal Coater 2-1 Unit
 - Total 6 Bottles of Manual Supply Type
- i. HMDS Supply System for 1 ADH Units in 2Block at Under Spin Unit